

Photomask Japan 2025 Program at a glance

As ofApril 7th

April 16 (Wed.)		April 17 (Thu.)		April 18 (Fri.)	
Annex Hall 2F/Room 1+2		Annex Hall 2F/Room 1		Annex Hall 2F/Room 2	
9:00 - 9:10	Opening				
9:10 - 10:55	<u>Session 1</u> Opening Session Day 1 Keynote & Mask Patterning with material Keynote Presenter: Martin van den Brink (ASML) Invited Talk Presenter: Kazunori Seki (Tekscend Photomask)	9:00 - 10:35 <u>Session 6</u> Opening Session Day 2 Keynote & MDP Keynote Presenter: Kenneth P. MacWilliams (Multibeam) Invited Talk Presenter: Kokoro Kato (synopsys)		9:00 - 10:35 <u>Session 7</u> Opening Session Day 2 Defect, Handling, Analysis and Pellicle Invited Talk Presenter: Takeshi Kondo (Lintec of America)	
10:55 - 11:25	Break	10:35 - 10:55 Break		10:35 - 10:55 Break	
11:25 - 12:25	<u>Session 2</u> Keynote & Energy Sustainability and Productivity Keynote Presenter: Mizuki Sakamoto (Tsukuba Univ.)	10:55 - 11:55 <u>Session 8</u> Mask Metrology		10:55 - 11:45 <u>Session 9</u> Resist related technologies Invited Talk Presenter: Kei Yamamoto (FUJIFILM)	
12:25 - 13:55	Lunch Break	11:55 - 13:25 Lunch Break		11:45 - 13:25 Lunch Break	
13:55 - 15:05	<u>Session 3</u> Large size panel technology Invited Talk Presenter: Ryoya Kitazawa (ulvac) Presenter: Charles Annis (OMDIA)	13:25 - 14:45 <u>Session 10</u> Mask Inspection Invited Talk Presenter: Safak Sayan (intel)		13:25 - 14:50 <u>Session11</u> NIL Invited Talk Presenter: Bríd Connolly (Tekscend Photomask) Presenter: Bo Zhao (Meta)	
15:05 - 15:25	Break	14:45 - 15:00 Break			
15:25 - 16:15	<u>Session 4</u> Mask Patterning 1 Invited Talk Presenter: Aki Fujimura (eBeam Initiative (D2S))	15:00 - 16:20 <u>Session 12</u> Poster Session		14:00 - 14:45 <u>Session 16</u> Laser Mask Writing Technology	
16:15 - 16:50	Break	16:20 - 16:40 Break		14:45 - 15:05 Break	
16:50 - 17:55	<u>Session 5</u> Mask repair Invited Talk (EMLC 2024 Best Poster) Presenter: Matthias Roesch (Carl Zeiss SMT)	16:40 - 18:10 Panel Discussion Talent recruiting, education and management in semiconductor/photomask industry		15:05 - 16:25 <u>Session 17</u> EB Mask Writing Technology Invited Talk Presenter: Christoph Spengler (IMS nanofabrication)	
		Conference Center 5F		16:25 - 16:35 Closing	
		18:30 - 20:30 Banquet			